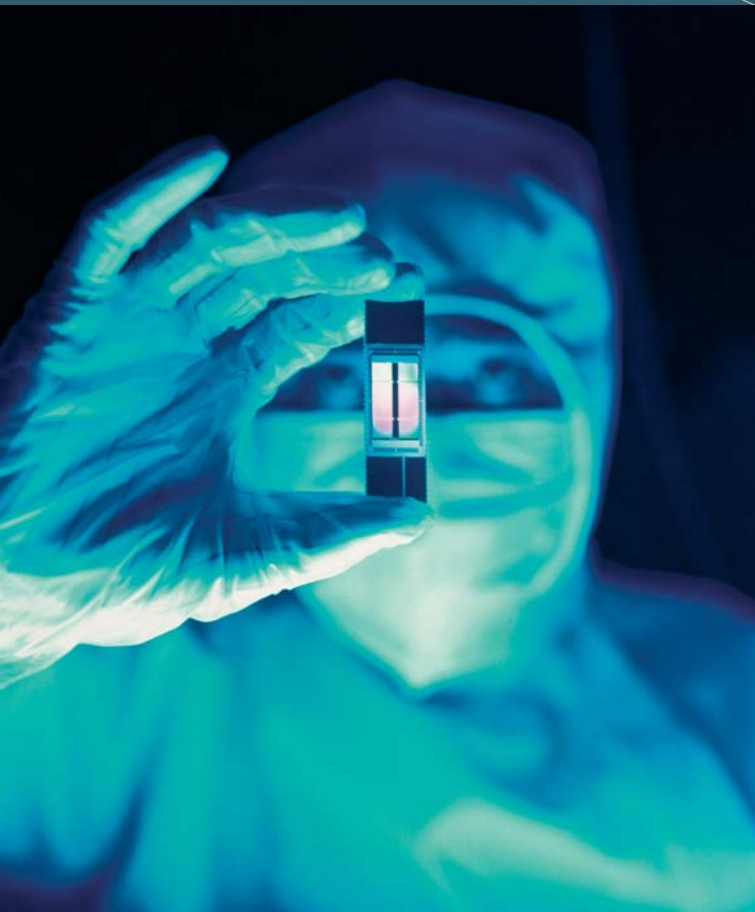


# <sup>11</sup>B in Form of Boron Trifluoride Gas for Semiconductor Manufacture



Boron Trifluoride gas is the ideal silicon wafer dopant for the production of highly integrated, high-density microchips. <sup>11</sup>B<sub>F<sub>3</sub></sub> provides for greater efficiency and increased production throughput, and helps to make chips smaller and better.

#### Specification

- Material <sup>11</sup>B - Boron 11 in form of Boron Trifluoride Electronic Grade
- Isotopic content <sup>11</sup>B > 99.9 at%
- BF<sub>3</sub> content <sup>11</sup>B > 99.99 wt%

#### Impurities in Vol. ppm

CO <sub>2</sub>	<	15
HF	<	15
N <sub>2</sub>	<	15
O <sub>2</sub> + Ar	<	15
SO <sub>2</sub>	<	10
SiF <sub>4</sub>	<	25

\* Our gas is fully compatible with VLIS-requirements.

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